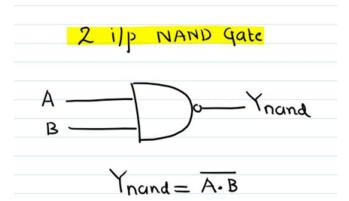
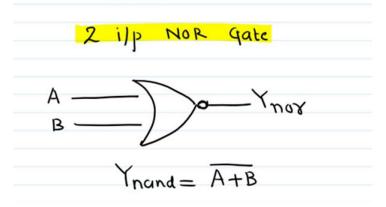
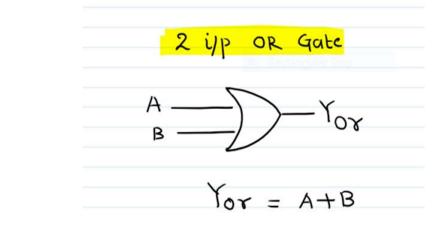
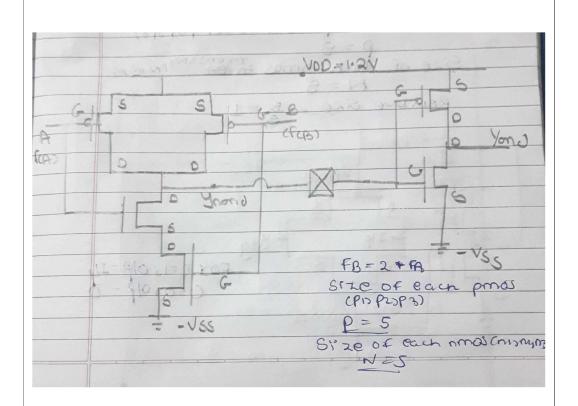
	ı	
Class	:	
Batch	:	
Roll. No	:	
ABC ID	:	
Assignment No.	:	B.1.b , B.1.c
Assignment Name	:	
Assignment Name	-	CMOS NAND-AND , CMOS NOR-OR Gate
Date Of Performance	:	

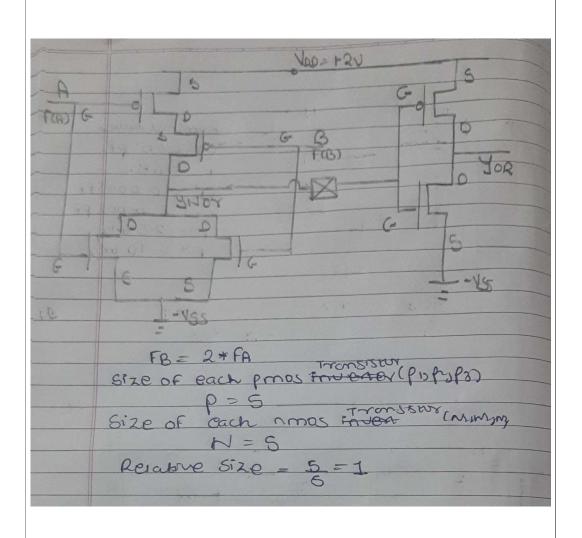
Block Diagram:-











Truth Tables :-

I/P's are ALWAYS STRONG
O/P :: S-1 = STRONG -1 , S-0 = STRONG - 0

1) 2 i/p NAND Gate:

Α	В	Ynand
0	0	S-1
0	1	S-1
1	0	S-1
1	1	S-0

2) 2 i/p AND Gate:

Α	В	Yand
0	0	S-0
0	1	S-0
1	0	S-0
1	1	S-1

3) 2 i/p NOR Gate

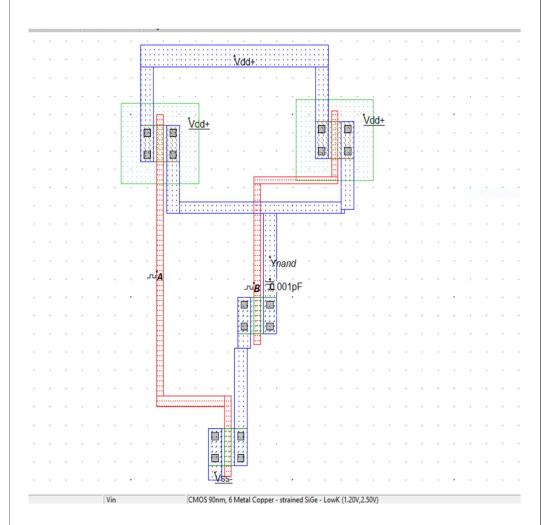
A_nor	B_nor	Ynor
0	0	S-1
0	1	S-0
1	0	S-0
1	1	S-0

4) 2 i/p OR Gate:

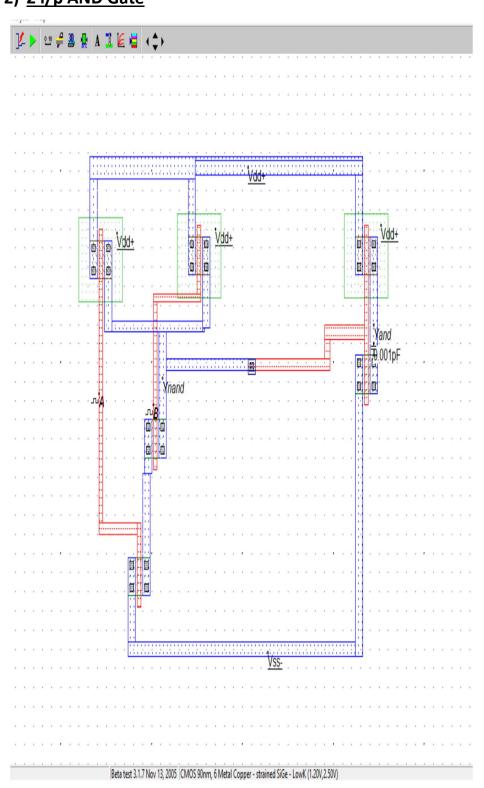
A_nor	B_nor	Yor
0	0	S-0
0	1	S-1
1	0	S-1
1	1	S-1

<u>Layout (90 nm Foundry</u>): (V_{dd} = 1.2 V)

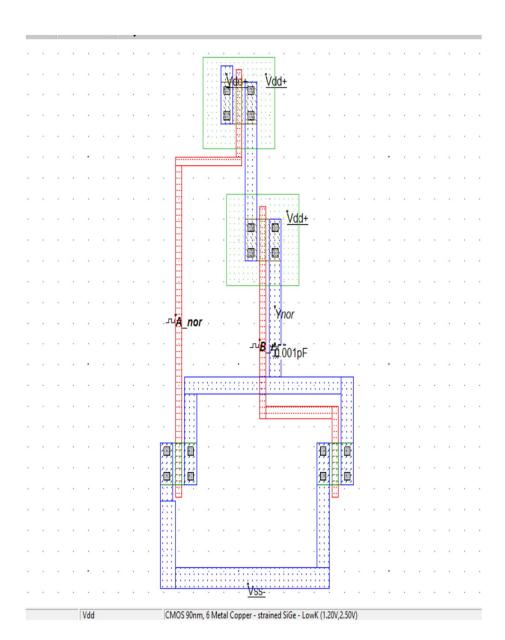
1) 2 i/p NAND Gate



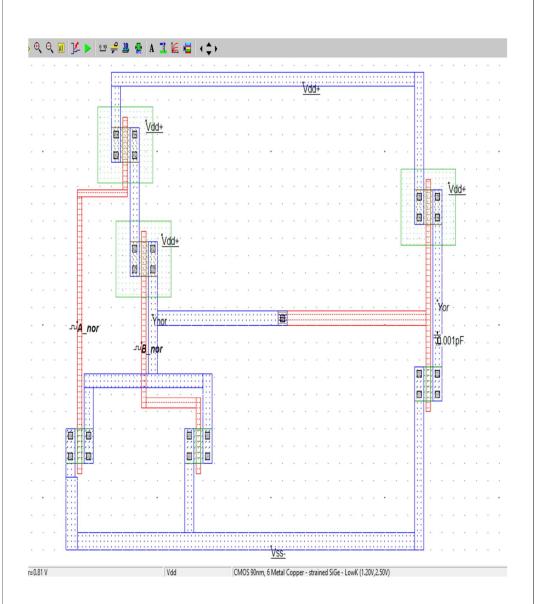
2) 2 i/p AND Gate



3) 2 i/p NOR Gate

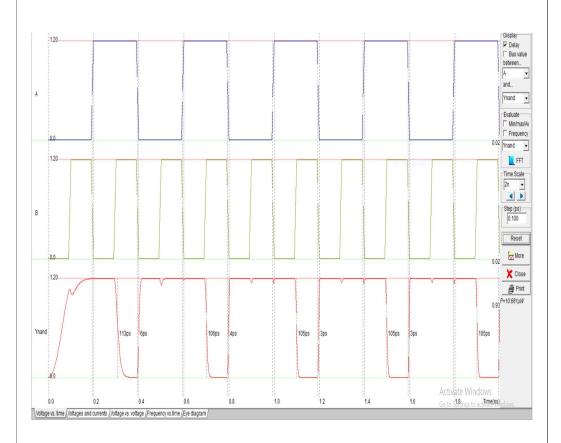


4) 2 i/p OR Gate

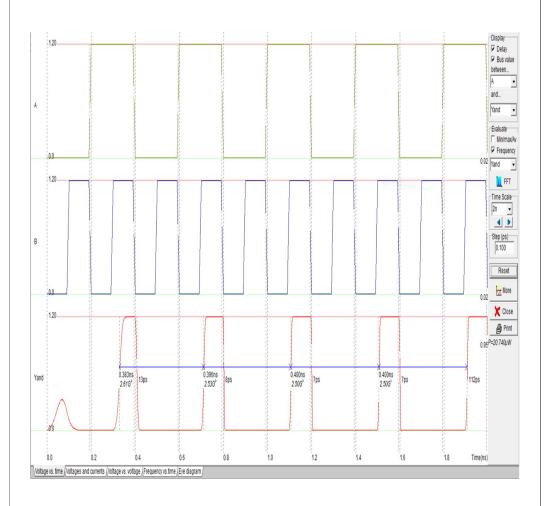


Waveforms:

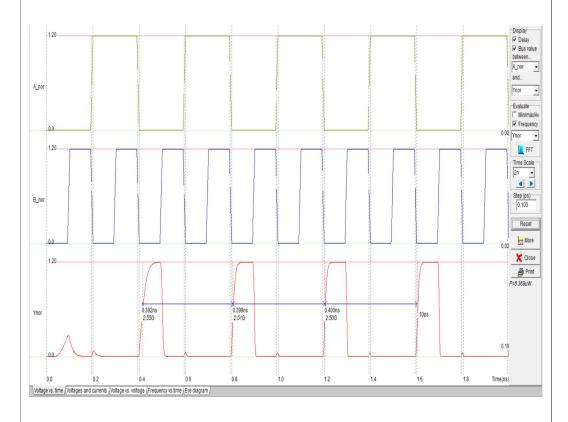
1) 2 i/p NAND Gate



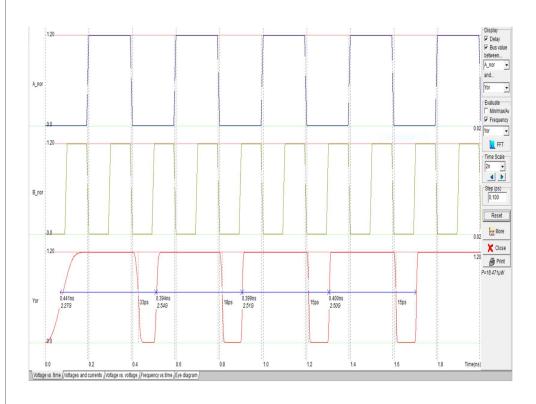
2) 2 i/p AND Gate



3) 2 i/p NOR Gate



4) 2 i/p OR Gate



Conclusion:-

- 1) Drawn the LAYOUT for CMOS 2 i/p NAND , AND , NOR , OR Gates using 90 nm Foundry.
- 2) NAND, NOR Gates have 2 P-channel Devices in PARALLEL, SERIES in PUN, PDN, respectively.
- 3) NAND, NOR Gates have 2 N-channel Devices in SERIES, PARALLEL in PUN, PDN, respectively.
- 4) AND, OR Gates are obtained by cascading NAND, NOR gates with NOT gate.
- 5) **O/P** of NAND, NOR Gate (On **METAL-1 Layer**) is connected to **I/P** of NOT gate (on **PolySilicon Layer**) using **METAL-1 To PolySilicon Contact**.
- 6) Kept Frequency of 1^{st} i/p (A) half that of frequency of 2^{nd} i/p (B).
- 7) Simulated the LAYOUT to observe waveforms & verified its functionality as per TRUTH-TABLE.
- 8) Being a **Pure-CMOS System** (PMOS // NMOS & CMOS INVERTER) , it gives both **S-1** & **S-0** as O/P.